

## **LISTING OF THE CLAIMS**

This listing of claims will replace all prior versions, and listings, of claims in the application:

### **Claims 1 - 16 (Canceled)**

### **Claim 17 (Currently Amended)**

A substrate processing apparatus comprising:

an alkaline developing unit ~~containing an alkaline developing solution~~ for performing an alkaline developing process for a substrate, said alkaline developing unit receiving an alkaline developing solution from an alkaline solution supplier that contains said alkaline developing solution;

an organic developing unit for performing an organic developing process for a substrate, said organic developing unit receiving an organic developing solution from an organic solution supplier that contains said organic developing solution;

a high-pressure processing unit for allowing a high-pressure fluid or a mixture of the high-pressure fluid and a chemical agent, as a processing fluid, to contact a surface of said developed substrate thereby performing a predetermined surface treatment for said developed substrate; and

a transport unit common to said alkaline developing unit and said organic developing unit ~~plural developing units~~, capable of accessing said alkaline developing unit, said organic developing unit, plural developing units and said high-pressure processing unit, for unloading the developed substrate from said alkaline developing unit and said organic developing unit ~~any one of said plural developing units~~ and for loading said developed substrate into said high-pressure processing unit,

wherein each of said alkaline developing unit and said organic developing unit ~~plural developing units~~ includes:

developing solution supply means for dispensing ~~supplying~~ the corresponding said developing solution to said substrate;

rinse liquid supply means for ~~dispensing~~ ~~supplying~~ a rinse liquid to said substrate; and  
replacing solution supply means for ~~dispensing~~ ~~supplying~~ a replacing solution having a composition which is different from that of said rinse liquid to said substrate thereby replacing said rinse liquid with said replacing solution;

wherein said alkaline developing unit and said organic developing unit ~~plural developing units~~ each perform a replacing process as a final processing of said developing process for replacing the solution adhered to said substrate, with said replacing solution being common to said alkaline developing unit and said organic developing unit ~~plural developing units~~.

**Claim 18 (Currently Amended)**

The substrate processing apparatus according to claim 17, wherein said transport unit wet-transport said developed substrate from any one of said alkaline developing unit and said organic developing unit ~~plural developing units~~ to said high-pressure processing unit.

**Claim 19 (Currently Amended)**

The substrate processing apparatus according to claim 17, comprising a plural number of said high-pressure processing units,

wherein said transport unit is capable of accessing said plural high-pressure processing units for unloading said developed substrate from any one of said alkaline developing unit and said organic developing unit ~~plural developing units~~ and for loading said developed substrate selectively to one of said plural high-pressure processing units.

**Claim 20 (Canceled)**

**Claim 21 (Currently Amended)**

A substrate processing apparatus comprising:

an alkaline developing unit containing an alkaline developing solution for performing an alkaline developing process for a substrate, said alkaline developing unit receiving an alkaline

developing solution from an alkaline solution supplier that contains said alkaline developing solution;

an organic developing unit ~~containing an organic developing solution~~ for performing an organic developing process for a substrate, said organic developing unit receiving an organic developing solution from an organic solution supplier that contains said organic developing solution;

a replacing unit for replacing a solution component adhered to said developed substrate with a replacing solution;

a high-pressure processing unit for allowing a high-pressure fluid or a mixture of a high-pressure fluid and a chemical agent, as a processing fluid, to contact a surface of said substrate subjected to the replacing process thereby performing a predetermined surface treatment for said substrate subjected to the replacing process; and

a transport unit common to said alkaline developing unit and said organic developing unit ~~plural developing units~~, capable of accessing said alkaline developing unit, said organic developing unit ~~plural developing units~~, said replacing unit and said high-pressure processing unit, for unloading the developed substrate from said alkaline developing unit and said organic developing unit ~~any one of said plural developing units~~ and for loading said developed substrate into said replacing unit and for unloading the substrate subjected to the replacing process from said replacing unit and for loading said substrate subjected to the replacing process into said high-pressure processing unit,

wherein each of said alkaline developing unit and said organic developing unit ~~plural developing units~~ includes:

developing solution supply means for ~~supplying~~ dispensing the corresponding ~~said~~ developing solution to said substrate; and

rinse liquid supply means for ~~supplying~~ dispensing a rinse liquid to said substrate,

wherein said replacing solution has a composition which is different from that of said rinse liquid; and

wherein said replacing unit performs a replacing process for replacing the solution adhered to said substrate; with said replacing solution being common to said alkaline developing unit and said organic developing unit ~~plural developing units~~.

**Claim 22 (Previously Presented)**

The substrate processing apparatus according to claim 21, wherein said transport unit wet-transportes said substrate among said plural developing units, said replacing unit and said high-pressure processing unit.

**Claim 23 (Previously Presented)**

The substrate processing apparatus according to claim 21, comprising a plural number of said high-pressure processing units,

wherein said transport unit is capable of accessing said plural high-pressure processing units for unloading said substrate subjected to the replacing process from said replacing unit and for loading said substrate selectively to one of said plural high-pressure processing units.

**Claims 24-27 (Canceled)**

**Claim 28 (Currently Amended)**

The substrate processing apparatus according to claim 17, wherein said replacing solution is liquid for preventing said substrate from becoming air-dry during the transportation of the substrate from any one of said alkaline developing unit and said organic developing unit ~~plural developing units~~ to said high-pressure processing unit.

**Claim 29 (Previously Presented)**

The substrate processing apparatus according to claim 21, wherein said replacing solution is liquid for preventing said substrate from becoming air-dry during the transportation of the substrate from said replacing unit to said high pressure processing unit.